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INFORMATION DISCLOSURE
CITATION

PTO-1449

Atty. Docket No.

NMTC-0771

Serial No.

10/098,713

Applicant

MACLEAN, Kevin

Filing Date

3/15/2002

Group

2818-2825

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<i>RD</i>	5,182,718	1/26/1993	Harafuji, et al.	364	490	3/29/1990
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<i>RD</i>	5,533,148	7/2/1996	Sayah, et al.	382	240	9/30/1993
<i>RD</i>	5,538,815	7/23/1996	Oi, et al.	430	5	9/14/1993
<i>RD</i>	5,631,110	5/20/1997	Shioiri, et al.	430	5	6/5/1995
<i>RD</i>	5,657,235	8/12/1997	Liebmann, et al.	364	474.24	5/3/1995
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<i>RD</i>	5,723,233	3/3/1998	Garza, et al.	430	5	2/27/1996
<i>RD</i>	5,815,685	9/29/1998	Kamon	395	500	9/15/1995
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<i>RD</i>	6,077,310	6/20/2000	Yamamoto, et al.	716	19	1/29/1999
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<i>PR</i>	Precim, "Proxima Wafer Proximity Correction System", Precim Company, Portland, Oregon (2 pages). <i>NO DATE.</i>
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<i>PR</i>	Cobb, et al., "Fast Sparse Aerial Image Calculation for OPC", SPIE, Vol. 2621, pp. 534-544, September 20-22, 1995.
<i>PR</i>	Lucas, K., et al., "Model Based OPC for 1st Generation 193nm Lithography", Motorola Inc., IDT assignee to IMEC (12 pages). <i>NO DATE.</i>
<i>PR</i>	Stimiman, J., et al., "Quantifying Proximity and Related Effects in Advanced Wafer Processes", Precim Company, Hewlett Packard Labs (9 pages). <i>NO DATE.</i>
<i>PR</i>	Sugawara, M., et al., "Practical Evaluation of Optical Proximity Effect Correction by EDM Methodology", Sony Corporation (11 pages).
<i>PR</i>	Saleh, B., et al., "Reduction of Errors of Microphotographic Reproductions by Optimal Corrections of Original Masks", Optical Engineering, Vol. 20, No. 5, pp. 781-784, September/October 1981.
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<i>PR</i>	Harafuji, K., et al., "A Novel Hierarchical Approach for Proximity Effect Correction in Electron Beam Lithography", IEEE, Vol. 12, No. 10, pp. 1508-1514, October 1993.
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						YES	NO
<i>[Signature]</i>	JP 3-80525	4/5/1991	JP	H01L	21/27	<input checked="" type="checkbox"/>	<input type="checkbox"/>
<i>[Signature]</i>	WO 00/67074 A1	11/9/2000	WO	G03F	7/20	<input checked="" type="checkbox"/>	<input type="checkbox"/>
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		Filing Date 3/15/2002	Group 2825
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<i>PD</i>	6,339,836 B1	1/15/2002	Eisenhofer, et al.	716	5	8/24/1998		
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